

Supply Chain Explorer

By the Emerging Technology Observatory

This is an export from the ETO Supply Chain Explorer, available at: <https://chipexplorer.eto.tech> You can see the web version of this content at <https://chipexplorer.eto.tech/?filter-choose=input-resource&input-resource=N90>.

CMP materials

Chemical mechanical planarization (CMP) is a process that makes layers produced during fabrication flat so lithography can successfully be performed on them. The highest-value materials used in chemical mechanical planarization are chemical slurries, which often include rare earth minerals, and polishing pads. During fabrication, a wafer is placed on the pad along with the slurry, and a polishing head presses against the wafer and rotates to planarize the wafer.

Country provision

- China (mainland)
- France
- Japan
- United States

Notable supplier companies

- Anji - China (mainland)
- CMC - United States
- DuPont - United States
- Fujifilm Electronic Materials - Japan
- Fujimi - Japan
- Hitachi - Japan
- Hubei Dinglong - China (mainland)
- JSR - Japan
- Merck Group - Germany
- Pureon - United States
- Saint-Gobain - France
- Thomas West - United States
- Versum Materials - United States